

Title (en)

ULTRA HIGH VOID VOLUME POLISHING PAD WITH CLOSED PORE STRUCTURE

Title (de)

POLIERKISSEN MIT ULTRAHOHEM LEERVOLUMEN UND GESCHLOSSENER PORENSTRUKTUR

Title (fr)

TAMPON DE POLISSAGE À VOLUME DE VIDE ULTRA-ÉLEVÉ PRÉSENTANT UNE STRUCTURE DE PORES FERMÉS

Publication

EP 3036760 A4 20170503 (EN)

Application

EP 14837394 A 20140821

Priority

- US 201313973639 A 20130822
- US 2014052021 W 20140821

Abstract (en)

[origin: US2015056895A1] The invention provides a polishing pad for chemical-mechanical polishing comprising a porous polymeric material, wherein the polishing pad comprises closed pores and wherein the polishing pad has a void volume fraction of 70% or more. Also disclosed is a method for preparing the aforesaid polishing pad and a method of polishing a substrate by use of theaforesaid polishing pad.

IPC 8 full level

B24B 37/24 (2012.01); **H01L 21/304** (2006.01)

CPC (source: CN EP US)

B24B 37/24 (2013.01 - CN EP US); **B24B 37/26** (2013.01 - CN); **B24D 11/001** (2013.01 - EP US)

Citation (search report)

- [XII] US 2005277371 A1 20051215 - PRASAD ABANESHWAR [US]
- See references of WO 2015027026A1

Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)

US 2015056895 A1 20150226; CN 105474366 A 20160406; CN 107520743 A 20171229; EP 3036760 A1 20160629; EP 3036760 A4 20170503; JP 2016528054 A 20160915; JP 2019171567 A 20191010; JP 6693875 B2 20200513; KR 20160045092 A 20160426; SG 10201801419X A 20180328; SG 11201601177S A 20160330; TW 201519999 A 20150601; TW I600501 B 20171001; WO 2015027026 A1 20150226

DOCDB simple family (application)

US 201313973639 A 20130822; CN 201480046528 A 20140821; CN 201710887971 A 20140821; EP 14837394 A 20140821; JP 2016536441 A 20140821; JP 2019088323 A 20190508; KR 20167007013 A 20140821; SG 10201801419X A 20140821; SG 11201601177S A 20140821; TW 103129117 A 20140822; US 2014052021 W 20140821